Inventor: Cem Basceri et. al.

Title: Circuit Constructions

Assignee: Micron Technology, Inc.

INFORMATION DISCLOSURE STATEMENT PURSUANT TO 37 C.F.R. §§1.56, 1.97 AND 1.98

In compliance with 37 C.F.R. §§1.56, 1.97 and 1.98, your attention is directed to the United States patents and other references listed on the attached Form PTO-1449.

The listed references were cited by, or submitted to, the Office in the parent, co-pending application of the above-identified application. The above-identified application is a divisional application of U.S. Patent Application Serial No. 10/443,354, which was filed May 21, 2003, which is a continuation-in-part application of U.S. Patent Application Serial No. 10/243,386, filed September 13, 2002; which is a divisional application of U.S. Patent Application Serial No. 09/827,759, filed April 6, 2001 and now U.S. Patent Number 6,511,896. Such prior disclosure is sufficient for the above-identified application as far as copies of the references are concerned. 37 C.F.R. §1.98(d) and MPEP §609(2). No admission is made regarding whether all the submitted references are prior art.

Citation of these references is respectfully requested.

Respectfully submitted,

Dated: 3/25/2004 Attorney:

David G. Latwesen, Ph.D.

Reg. #38,533

WELLS ST. JOHN P.S.

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Form PTO-1449				U.S. DEPARTMENT OF COMME PATENT AND TRADEMARK OFF			ATTY, DOCKET NO. MI22-2515	PRIO 10/44)	PRIORITY SERIAL NO. 10443,354			
		LI	ST OF ART CITED (Use several sheets		APPLICANT Cem Basceri et al.							
	-						PRIORITY FILING DATE May 21, 2003			PRIORITY GROUP		
. U.S. PATENT DOCUMENTS												
*Examiner Initial		Document Number		Date	Name .			Class	Subclass	Filing If Appro	Filing Date If Appropriate	
	AA	5,292,673		03-1994	Shinriki et al.							
	AB	5,486,488		01-1996	Kamiyama							
	AC	5,641,702		06-1997	lmai et al.						,	
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	АН	6,235,572		05-2001	Kunitomo et al.							
	Al	6,399,438		06-2002	Saito et al.							
	, TA	6,511,896		1/28/03	Basceri et al.							
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		Document Number		Date	· Country			Class	Subclass	Trans Yes	lation No	
	AK											
	AL											
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)												
	АМ		Bin Yu, et al., "70nm MOSFET with Ultra-Shallow, Abrupt, and Super-Doped S./D Extension Implemented by Laser Thermal Process (LTP)", IEEE, 03/1999.									
	AN	Somit Talwar, et al., "Ultra-Shallow, Abrupt, and Highly-Activated Junctions by Low-Energy Ion Implantation and Laser Annealin Verdant Technologies, San Jose, CA.										
	AO		Ken-ichi Goto, et al., "Ultra-Low Contact Resistance for Deca-nm MOSFETs by Laser Annealing", IEEE, 09/1999, pps. 20.7.1-20.7.3.									
EXAMINER						DATE CONSIDERED						
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.												